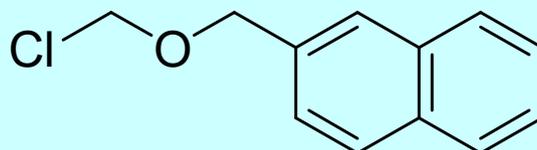


MBom基に代わる新規Bom系保護基
MBom-Clより安定で、用時調製不要！

NAPOM-Cl

2-Naphthylmethoxymethylchloride

酸化的条件で除去できる新規Bom系保護基で、アルコール、カルボン酸、フェノール、チオールの保護基として使用できます。



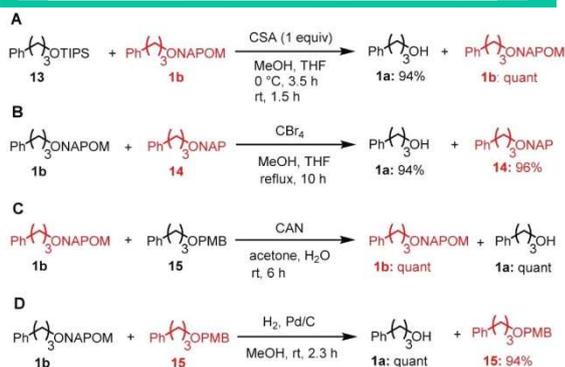
特長

- ・NAP基やPMB基との外し分けが可能
- ・導入・除去に様々な溶媒が使用可能

Code	A00792	
CAS No.	914300-10-0	
Price	1 g	¥ 15,000
	5 g	¥ 45,000

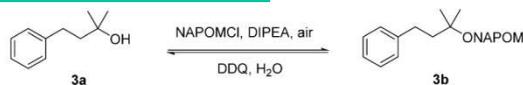
※安定剤として塩化カルシウムを含みます。

● NAPOM基と他の保護基の外し分け ●



^a1:1 (mol/mol) mixture of substrates was used. For each entry, compounds whose protecting groups remained untouched are highlighted in red.

● 溶媒の許容性 ●

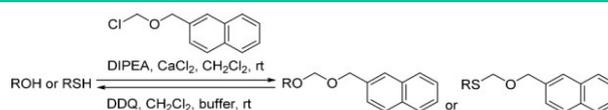


solvent	introduction		removal	
	reaction time/h	yield/% ^a	reaction time/h	yield/%
hexane	50	77	15	87 ^c
toluene	15.5	93	11.5	86 ^c
MTBE	109	83	109	99 ^c
CH ₂ Cl ₂	39	97	2	91 ^b
AcOEt	50	92	17	97 ^c
THF	109	85	109	25 ^c
CH ₃ CN	109	78	17.5	98 ^c
DMF	109	82	109	31 ^c
DMSO	109	72	109	63 ^c

^a3 equiv of NAPOMCl and 6 equiv of DIPEA were used. ^b1.5 equiv of DDQ were used. ^c2.5 equiv of DDQ were used.

been reported to date. First, the introduction of the NAPOM group onto monoacetylated diol 7 was attempted under the conventional conditions using DIPEA (entry 1 of Table 3).

● NAPOM基の-OH基、-SH基への導入・除去 ●



entry	substrate	yield / % ^a	
		introduction ^b	removal ^c
1		91	98
	1a: R = H 1b: R = NAPOM		
2		90	96
	2a: R = H 2b: R = NAPOM		
3		96	91
	3a: R = H 3b: R = NAPOM		
4		94	88
	4a: R = H 4b: R = NAPOM		
5		91 ^d	quant ^e
	5a: R = H 5b: R = NAPOM		
6		88	6c: 94
	6a: R = H 6b: R = NAPOM 6c: R = SCH ₂ CH ₂ Ph		

^aIsolated yields, after silica gel column chromatography. ^bNAPOMCl (1.8 to 3 equiv), DIPEA (4 to 6 equiv), CaCl₂ (100 wt %), CH₂Cl₂ (subs. concn 0.1 M), rt, 6.5 to 32.5 h. ^cDDQ (1.5 equiv), CH₂Cl₂/phosphate buffered water (pH 7.0) = 18/1, rt, 2 to 3.5 h. ^dPurified by recrystallization. ^eDDQ (2.0 equiv), CH₂Cl₂/pH 7.0 buffer, rt, 22.5 h.

Reference: Sato, T. Oishi, T. and Torikai, K. (2015), *Org. Lett.*, 17, pp. 3110-3113. 特許出願済【特願2016-553062】.